

EAST Search History

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S77	6	("20010024867" "20010048973" "5932286").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/03/29 14:30
S78	13	("4200666" "6503557" "6566281" "6630413" "7510984").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/03/29 15:11
S79	6	("20030168707" "20040121085" "5508067").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/03/29 15:14
S80	4	"2003046254"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/03/29 16:07
S81	719	"427".clas. and (LPCVD or low pressure (CVD or chemical vapor deposition)) and (silicon nitride or SiN)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/03/29 16:16
S82	82	S81 and (trisilylamine or hydrazine or dimethylhydrazine or disilylmethylhydrazine)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/03/29 16:17
S83	18	("4200666").URPN.	USPAT	ADJ	ON	2011/03/29 16:20
S84	33	(LPCVD or low pressure (CVD or chemical vapor deposition)) same (silicon nitride or SiN) and (trisilylamine or disilylmethylhydrazine)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/03/29 16:36
S85	16	"1441042"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/03/29 16:43

S86	6	(LPCVD or low pressure (CVD or chemical vapor deposition)) same (silicon nitride or SiN) and hydrazinosilane	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/03/29 16:46
S87	6	(LPCVD or low pressure (CVD or chemical vapor deposition)) and hydrazinosilane	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/03/29 16:47
S88	67	(disilylmethylhydrazine or dimethylhydrazine) and (LPCVD or low pressure (CVD or chemical vapor deposition))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/03/29 16:48
S89	2	"20040121085".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/03/30 17:28
S90	2	"20030203653".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/03/30 17:30
S91	23	("4200666" "4980307" "5464783" "5508532" "5578530" "5663087" "5710067" "5837598" "5939763" "5969397" "6037651").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/03/30 17:41
S92	20	("3424661").PN. OR ("4200666").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2011/03/30 17:43
S93	18	"427".clas. and (low pressure (CVD or chemical vapor deposition) or LPCVD) and (trisilylamine or TSA)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/03/30 17:46

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SiN.silyhydrazine.wsp